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## Chapter 5: Temperature Dependence and Self-Heating

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Self-heating in SOI is more important than in bulk since the thermal conductivity of silicon dioxide is about two orders of magnitude lower than that of silicon [15]. It may degrade the carrier mobility, increase the junction leakage [20], enhance the impact ionization rate [24], and therefore affect the output characteristics [16] of floating-body SOI devices.

### 5.1. Temperature Dependence

The temperature dependence of threshold voltage, mobility, saturation velocity and series resistance in BSIMSOI is identical to BSIM3v3. However a different temperature dependence of diode characteristics is adopted in BSIMSOI4.0:

$$\begin{aligned}j_{sbjt} &= i_{sbjt} \exp \left[ \frac{-E_g(300K)}{n_{diodes} V_t} X_{bjt} \left( 1 - \frac{T}{T_{nom}} \right) \right] \\j_{dbjt} &= i_{dbjt} \exp \left[ \frac{-E_g(300K)}{n_{diodes} V_t} X_{bjt} \left( 1 - \frac{T}{T_{nom}} \right) \right] \\j_{sdif} &= i_{sdif} \exp \left[ \frac{-E_g(300K)}{n_{diodes} V_t} X_{dif} \left( 1 - \frac{T}{T_{nom}} \right) \right] \\j_{ddif} &= i_{ddif} \exp \left[ \frac{-E_g(300K)}{n_{diodes} V_t} X_{dif} \left( 1 - \frac{T}{T_{nom}} \right) \right] \\j_{srec} &= i_{srec} \exp \left[ \frac{-E_g(300K)}{n_{recf0s} V_t} X_{rec} \left( 1 - \frac{T}{T_{nom}} \right) \right] \\j_{drec} &= i_{drec} \exp \left[ \frac{-E_g(300K)}{n_{recf0d} V_t} X_{rec} \left( 1 - \frac{T}{T_{nom}} \right) \right] \\j_{stun} &= i_{stun} \exp \left[ X_{nun} \left( \frac{T}{T_{nom}} - 1 \right) \right]\end{aligned}$$

$$\begin{aligned}
 j_{dtun} &= i_{dtun} \exp \left[ X_{tun} \left( \frac{T}{T_{nom}} - 1 \right) \right] \\
 n_{recrs} &= n_{recr0s} \left[ 1 + nt_{recr} \left( \frac{T}{T_{nom}} - 1 \right) \right] \\
 n_{recrd} &= n_{recr0d} \left[ 1 + nt_{recr} \left( \frac{T}{T_{nom}} - 1 \right) \right] \\
 n_{recfs} &= n_{recf0s} \left[ 1 + nt_{recf} \left( \frac{T}{T_{nom}} - 1 \right) \right] \\
 n_{recfd} &= n_{recf0d} \left[ 1 + nt_{recf} \left( \frac{T}{T_{nom}} - 1 \right) \right]
 \end{aligned} \tag{5.1}$$

The parameters  $i_{s_{bjt}}, i_{s_{dbjt}}, i_{s_{dif}}, i_{s_{ddif}}, i_{s_{srec}}, i_{s_{drec}}, i_{s_{stun}}, i_{s_{dtun}}$  are diode saturation currents at the nominal temperature  $T_{nom}$ , and the parameters  $X_{bjt}, X_{dif}, X_{rec}, X_{tun}$  are provided to model the temperature dependence. Notice that the non-ideality factors  $n_{recfs}, n_{recfd}, n_{recrs}, n_{recrd}$  are also temperature dependent.

## 5.2. Self-Heating Implementation

BSIMPD/BSIMSOI models the self-heating by an auxiliary  $R_{th}C_{th}$  circuit as shown in Fig. 5.1 [18]. The temperature node (T node) will be created in SPICE simulation if the self-heating selector *shMod* is ON and the thermal resistance is non-zero. The T node is treated as a voltage node and is connected to ground through a thermal resistance  $R_{th}$  and a thermal capacitance  $C_{th}$ :

$$R_{th} = \frac{R_{th0}}{W_{eff}' + W_{th0}}, \quad C_{th} = C_{th0} (W_{eff}' + W_{th0}) \tag{5.2}$$

where  $R_{th0}$  and  $C_{th0}$  are normalized thermal resistance and capacitance, respectively.  $W_{th0}$  is the minimum width for thermal resistance calculation [19]. Notice that the current source is driving a current equal to the power dissipated in the device.

$$P = |I_{ds} \times V_{ds}| \tag{5.3}$$

To save computation time, the turn-on surface potential  $\phi_s$  ( $\Phi$ ) is taken to be a constant within each timepoint because a lot of parameters (e.g.  $X_{dep}$ ) are function of  $\phi_s$ . Each timepoint will use a  $\phi_s$  calculated with the temperature iterated in the previous timepoint. However this approximation may induce error in DC, transient and AC simulation. Therefore, it is a tradeoff between accuracy and speed. The error in DC or transient is minimal if the sweeping step or time step is sufficiently small.

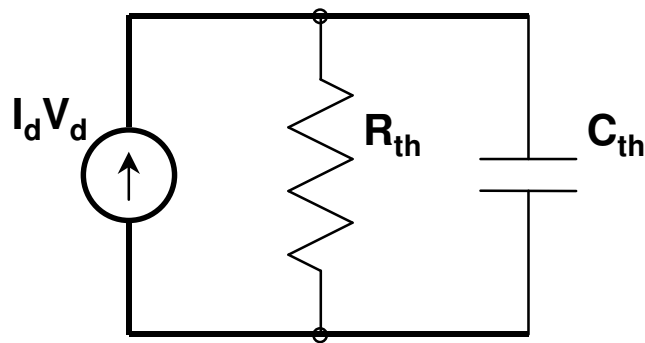


Fig. 5.1 Equivalent circuit for self-heating simulation.